

<b>Notice of References Cited</b>	Application/Control No. 10/077,720	Applicant(s)/Patent Under Reexamination SU ET AL.	
	Examiner Anita K Alanko	Art Unit 1765	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,495,469	12-2002	Yang et al.	438/725
*	B	US-6,383,919	05-2002	Wang et al.	438/638
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Li, Y.X. et al "Selective reactive ion etching of silicon nitride over silicon using CHF3 with N2 addition" JVSTB 13 (5) 2008-2012, September/October 1995.
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.